

Call for papers

IC-PLANTS 2008

The 1st International Conference on Plasma-Nanotechnology & Science

March 13-14, 2008

IB Building, Nagoya University, Nagoya JAPAN

Sponsored by Plasma Nanotechnology Research Center (PLANT), Nagoya University
Nagoya Industrial Science Research Institute

Co-Sponsored by The Hibi Science Foundation
In conjunction with Tokai division of the Japan Society of Applied Physics (tentative)

Plasma processing technologies are the state of the art technologies leading the way through ultra-high performance in Nano-materials, microelectronic devices, flat panels, etc.. IC-PLANTS is organized for offer an opportunity for discussions and exchange of recent progress of Plasma Science and Nanotechnology among the Plasma COEs in the world. It is absolutely necessary to collaborate between the research communities for clearing the complex issues in the interdisciplinary research fields. First IC-PLANTS is to be held in the Plasma Nanotechnology Research Center at Nagoya University, Japan. The Organizing Committee invites you to the conference and welcomes the submission of your papers.

General Topics and Panel discussion

Theme: Plasma nanotechnologies, processes and related technologies from fundamentals to applications

Topics: Nano-fabrication / Diagnostics and monitoring of plasmas and Reaction surfaces / Nano-electronics / Nano-biology / Interdisciplinary or integrated research with Plasma technologies / Nano-optics / NEMS technologies / Process technologies for flat panel display / Environmental technologies / Equipment technologies / Emerging new concept

Panel Discussion:

'FLUCTUATION' The last issue in Nanotechnology; Emerging mechanism and Solutions

Submission of Abstracts (Poster session only)

One page (A4) abstract should be submitted by **February 28, 2008** via the web.
Template is available at <http://www.plasma.engg.nagoya-u.ac.jp/IC-2008/> .

Invited Speakers from abroad (*Tentative*)

Uwe Czarnetzki (Ruhr-University Bochum, Germany)

R.A.H. Engeln (Eindhoven University of Technology, Netherlands)

Jeon G. Han (SungKyunKwan University, Korea)

Yidong Huang (Tsinghua University, China)

Olivier Joubert (Laboratoire des Technologies de la Microelectronique, CNRS, France)

Volker Brueser (Institute of Low Temperature Plasma Physics, Germany)

Registration Fee General : ¥15,000.-, Student : *Free*

Organizing Committee Chair

Yasuo Suzuoki, Director, Plasma Nanotechnology Research Center, Nagoya University

Conatct

Koichi Sasaki (Executive Committee Chair)

Makoto Sekine (Program Committee Chair)

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